

L Number	Hits	Search Text	DB	Time stamp
40	4	6156481.URPN.	USPAT	2003/06/16 09:10
41	6	("4491628" "4603101" "5252435" "5324804" "5942367" "6033828").PN.	USPAT	2003/06/16 09:12
42	2	("5145764").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/16 09:17
43	5	5145764.URPN.	USPAT	2003/06/16 09:15
44	8	("3779778" "4193797" "4491628" "4678737" "4887450" "4898803" "4916046" "4951379").PN.	USPAT	2003/06/16 09:16
45	2	("5891603").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/16 09:57
46	1	("5942367").PN.	USPAT	2003/06/16 09:57
-	219	((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:28
-	214	((((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:15
-	2	jp-10031310-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 16:24
-	2	ep-473547-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 18:37
-	112	((((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) and (branch branched)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:27
-	74	(t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:29
-	4	((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) and (\$5acid near generator) and solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:55
-	3911	branched near polymer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:55
-	3	(branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 16:23
-	5	(branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:57
-	5	((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) not ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 15:58
-	2	jp-10031310-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 16:30

EAST Search

Do Not Remove

-	150	SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 16:42
-	21	(SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 18:36
-	112	STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 18:42
-	10	(STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 18:42
-	4	4230645.URPN.	USPAT	2002/09/13 18:46
-	2	(acrylic near methacrylic near styrene) and (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 18:50
-	17	(acrylate near methacrylate near styrene) and (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:08
-	778	(styrene) and (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:03
-	646	((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:04
-	573	((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:05
-	571	(((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:05
-	293	(((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)) and (fluorine fluoro trifluoromethyl)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:07
-	4	(((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)) and (fluorine fluoro trifluoromethyl)) and (branched near polymer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:06

-	214	<p> ((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)) and (fluorine fluoro trifluoromethyl)) not (6300035.PN. (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) and (branch branched)) jp-10031310-\$.did. ep-473547-\$.did. ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) (((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) and (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist))) (branched near polymer) ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate))) ((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) (((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) not ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)))) jp-10031310-\$.did. (SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) ((SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) and (resist photoresist)) (STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) ((STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt))) </p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:08
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-	211	((((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)) and (fluorine fluoro trifluoromethyl)) not (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) and (branch branched)) jp-10031310-\$.did. ep-473547-\$.did. ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) and (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist))) (branched near polymer) ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate))) ((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) (((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) not ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)))) jp-10031310-\$.did. (SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) ((SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) and (resist photoresist)) (STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) ((STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:08
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-	211	<p> (((((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)) and (fluorine fluoro trifluoromethyl)) not (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) and (branch branched)) jp-10031310-\$.did. ep-473547-\$.did. ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) (((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) and (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist))) (branched near polymer) ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate))) ((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) (((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) not ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)))) jp-10031310-\$.did. (SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) ((SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) and (resist photoresist)) (STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) ((STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt))) not ((STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt)) </p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/13 19:09
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-	5	<p>(((((((styrene) and (\$5acid near generator)) and (acrylate methacrylate acrylic methacrylic)) and (resist photoresist)) and (polymer copolymer terpolymer tetrapolymer)) and (fluorine fluoro trifluoromethyl)) not (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist)) and (branch branched)) jp-10031310-\$.did. ep-473547-\$.did. ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) (((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)) and (((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)) and fluor\$8) and (substrate support) and (expos\$4) and (develop\$4) and (photoresist resist))) (branched near polymer) ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate))) ((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) (((branched near polymer) and ((acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent))) not ((branched near polymer) and ((t-butyl adj methacrylate) and (isobornyl adj methacrylate) and (2-hydroxyethyl adj methacrylate)))) jp-10031310-\$.did. (SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) ((SCHADT-III-FRANK SCHADT-III-FRANK-L SCHADT-III-FRANK-LEONARD FRYD-M FRYD-MICHAEL FRYD-MIKE PERIYASAMY PERIYASAMY-M PERIYASAMY-MOOKKAN) and (resist photoresist)) (STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) ((STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt))) not ((STEINMANN-A STEINMANN-ALBIN STEINMANN-ALFRED STEINMANN-ALFRED-DR) and (onium near salt))) and macromer</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/15 13:57
-	64	macromer and (ethylenically near unsaturated) and (addition near polymerization)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/15 14:04
-	3	(macromer and (ethylenically near unsaturated) and (addition near polymerization)) and (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/15 14:11

-	5	(macromer and (ethylenically near unsaturated) and (addition near polymerization)) and (\$5acid near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/15 14:11
-	2	((macromer and (ethylenically near unsaturated) and (addition near polymerization)) and (\$5acid near generat\$4)) not ((macromer and (ethylenically near unsaturated) and (addition near polymerization)) and (\$5acid near generator))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/15 14:11
-	302	(acid near labile) and (\$4acrylate) and (\$5acid near generat\$3) and (\$8styrene) and (solvent)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 12:11
-	1858	acryl\$4 near methacryl\$4 near (styrene (vinyl adj phenyl))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 12:24
-	46	(acryl\$4 near methacryl\$4 near (styrene (vinyl adj phenyl))) and (\$5acid near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 13:33
-	28	(fluorine near (polymer copolymer terpolymer)) and (\$5acid near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 13:46
-	155	430/907.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 13:47
-	154	430/907.ccls. not (((fluorine near (polymer copolymer terpolymer)) and (\$5acid near generat\$4)) ((acryl\$4 near methacryl\$4 near (styrene (vinyl adj phenyl))) and (\$5acid near generat\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 13:52
-	13	((("6280897") or ("4665144") or ("6291130") or ("6303265") or ("6291129") or ("6280897") or ("6200728")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:07
-	2	("5100762").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:12
-	4	((("5861231") or ("4613657")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:48
-	1	us-20010010890-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:49
-	1	us-20010010890-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:51
-	1	us-20010010890-\$.did. us-20010010890-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:50
-	2	us-20010018162-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:51
-	3	us-20010010890-\$.did. us-20010018162-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/16 14:51
-	2231	macromer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:13

-	4573	(branched near polymer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:13
-	398590	(photoresist resist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:14
-	15853	(photoacid acid) near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:16
-	1	macromer and ((branched near polymer)) and ((photoresist resist)) and ((photoacid acid) near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:17
-	29	((branched near polymer)) and ((photoresist resist)) and ((photoacid acid) near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:39
-	0	200025178.URPN.	USPAT	2003/06/10 11:38
-	6	backbone same sidearms	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 11:39
-	6	backbone same sidearm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 12:18
-	0	200025178.URPN.	USPAT	2003/06/10 12:17
-	4027	macromonomer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 12:18
-	275	macromonomer and ((photoresist resist))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 12:19
-	24	(macromonomer and ((photoresist resist))) and ((photoacid acid) near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 12:19
-	23	((macromonomer and ((photoresist resist))) and ((photoacid acid) near generat\$3)) not ((backbone same sidearm) (((branched near polymer)) and ((photoresist resist)) and ((photoacid acid) near generat\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 12:19
-	2047	branched same graft	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:29
-	9627	backbone same (graft pendant)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:29
-	2588	(branched comb) same graft	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:30
-	11640	(backbone same (graft pendant)) ((branched comb) same graft)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:30
-	1430	((backbone same (graft pendant)) ((branched comb) same graft)) and (photoresist resist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:35
-	459	((backbone same (graft pendant)) ((branched comb) same graft)) and (photoresist resist)) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:35

-	32256	macromer macromonomer (branched near segment) (sidearm (side adj arm) side-arm)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:34
-	42806	((backbone same (graft pendant)) ((branched comb) same graft)) (macromer macromonomer (branched near segment) (sidearm (side adj arm) side-arm))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:34
-	3351	((backbone same (graft pendant)) ((branched comb) same graft)) (macromer macromonomer (branched near segment) (sidearm (side adj arm) side-arm))) and (photoresist resist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:35
-	534	((backbone same (graft pendant)) ((branched comb) same graft)) (macromer macromonomer (branched near segment) (sidearm (side adj arm) side-arm))) and (photoresist resist)) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:35
-	457	((backbone same (graft pendant)) ((branched comb) same graft)) (macromer macromonomer (branched near segment) (sidearm (side adj arm) side-arm))) and (photoresist resist)) and (430/\$.ccls.) and (acrylate methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:38
-	3820	(acid photoacid) near generator	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:38
-	1071	photoactive adj compound	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:41
-	4682	((acid photoacid) near generator) (photoactive adj compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 19:42
-	197	((backbone same (graft pendant)) ((branched comb) same graft)) (macromer macromonomer (branched near segment) (sidearm (side adj arm) side-arm))) and (photoresist resist)) and (430/\$.ccls.) and (acrylate methacrylate)) and ((acid photoacid) near generator) (photoactive adj compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 20:51
-	10	(("20010038971") or ("20010033994") or ("6551758") or ("6156481") or ("5891603")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 21:42
-	0	2000199960.URPN.	USPAT	2003/06/13 22:08
-	0	2000199960.URPN.	USPAT	2003/06/13 22:07
-	14	(("4491628") or ("4603101") or ("5252435") or ("5324804") or ("5942367") or ("6033828")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/13 22:08